

ECE 340 Lecture 14

Semiconductor Electronics

Spring 2022

10:00-10:50am

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Today's Discussion

- **Summary of previous lecture:**
 - **Optical absorption**
 - **Direct Recombination of Electrons and Holes**
- **Steady State Carrier Generation**
- **Photoconductive Devices**

Quick Recap

We have introduced the following optical processes in a semiconductor material:

- 1. Absorption of light as a function of space**
- 2. Recombination process after a uniform distribution of excess carriers has been generated (and the illumination is abruptly interrupted)**

Today we will discuss a third process:

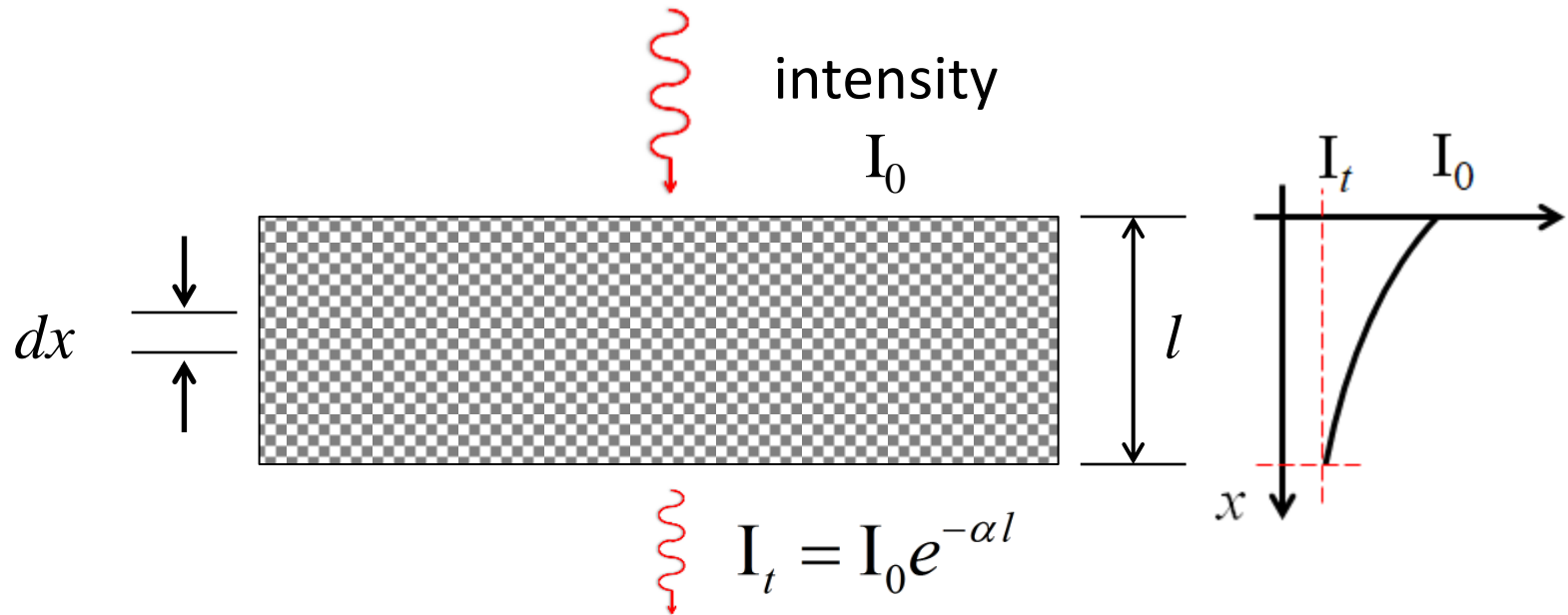
- 3. Steady-state generation of excess carriers under continuous illumination**

1. Optical Absorption

I_0 [photons/cm²-s]

α = absorption coefficient

$$h\nu > E_g$$



$$-\frac{d I(x)}{dx} = \alpha I(x) \quad \Rightarrow \quad I(x) = I_0 e^{-\alpha x}$$

2. Recombination of Electrons and Holes

$$h\nu > E_g$$



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Now we pump electrons into the conduction band by a short flash of light that ends at $t = 0$

initial condition

$$t = 0$$

$$\Delta n = \Delta p = \text{initial excess concentration}$$

$\delta n(t)$ = instantaneous concentration of excess electrons

$\delta p(t)$ = instantaneous concentration of excess holes

$$\text{assumption} \quad \delta n(t) = \delta p(t)$$

We have obtained the evolution equation

$$\frac{d \delta n(t)}{d t} = -\alpha_r \left[(n_o + p_o) \delta n(t) + \delta n^2(t) \right]$$

2. Recombination of Electrons and Holes

$$\frac{d \delta n(t)}{d t} = -\alpha_r \left[(n_o + p_o) \delta n(t) + \cancel{\delta n^2(t)} \right]$$

Last term can be neglected in the case of “low level injection”

$$\delta n^2(t) \ll (n_o + p_o) \delta n(t)$$

$$\delta n(t) \ll (n_o + p_o)$$

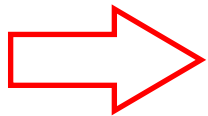
In extrinsic semiconductor, we can predict the decay of minority carrier concentration due to recombination.

Low-level injection conditions → Simplification

$$\frac{d \delta n(t)}{d t} = -\alpha_r \left[(n_o + p_o) \delta n(t) + \underbrace{\delta n^2(t)}_{\text{can be neglected}} \right]$$

Extrinsic semiconductor p -type

$$\frac{d \delta n(t)}{d t} \simeq -\alpha_r p_o \delta n(t) \quad p_o \gg n_o \quad \text{Neglect equilibrium minority carriers}$$



$$\delta n(t) = \underbrace{\Delta n}_{\text{initial condition}} \exp(-\alpha_r p_o t) = \Delta n \exp\left(-\frac{t}{\tau_n}\right)$$

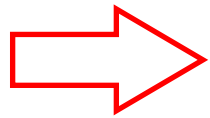
$$\tau_n = \frac{1}{\alpha_r p_o} = \text{minority recombination lifetime}$$

Low-level injection conditions → Simplification

$$\frac{d \delta n(t)}{d t} = -\alpha_r \left[(n_o + p_o) \delta n(t) + \underbrace{\delta n^2(t)}_{\text{can be neglected}} \right]$$

Extrinsic semiconductor *n*-type

$$\frac{d \delta p(t)}{d t} \simeq -\alpha_r n_o \delta p(t) \quad n_o \gg p_o \quad \text{Neglect equilibrium minority carriers}$$



$$\delta p(t) = \underbrace{\Delta p}_{\text{initial condition}} \exp(-\alpha_r n_o t) = \Delta p \exp\left(-\frac{t}{\tau_p}\right)$$

$$\tau_p = \frac{1}{\alpha_r n_o} = \text{minority recombination lifetime}$$

Low level injection conditions → Simplification

More generally you can use this formula

$$\tau = \frac{1}{\alpha_r (n_o + p_o)}$$

It works for both p - and n -type material in low level injection conditions

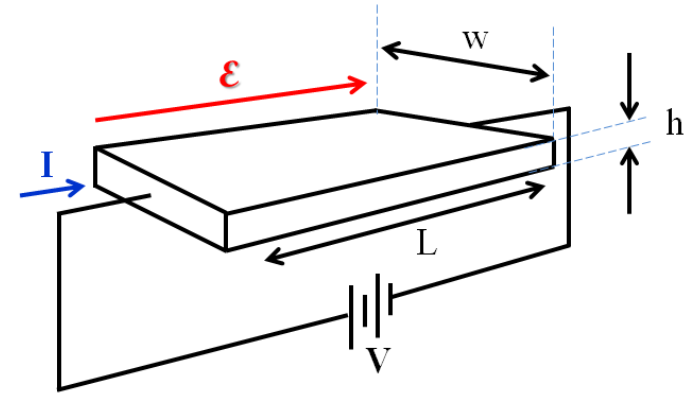
Remember this problem?

- Resistivity**

$$\rho = \frac{1}{q\mu_n n_i + q\mu_p n_i} = \frac{1}{qn_i(\mu_n + \mu_p)} =$$
$$= \frac{1}{1.6 \times 10^{-19} \times 1.5 \times 10^{10} (1350 + 480)} = 227.4 \text{ k}\Omega \cdot \text{cm}$$

$$R = \rho \frac{L}{A} = 227.4 \times 10^3 \frac{1.0}{10^{-2}} = 22.74 \times 10^6 = 22.74 \text{ M}\Omega$$

$$I = \frac{V}{R} = \frac{10}{22.74 \times 10^6} = 0.44 \mu\text{A}$$



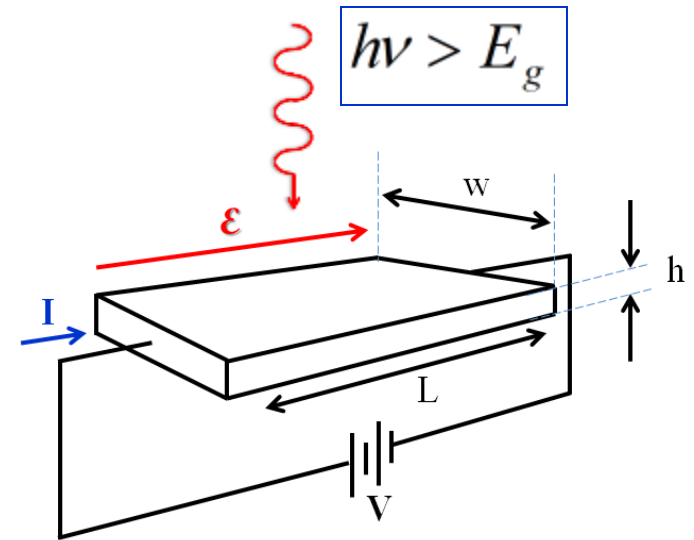
Can we increase the current somehow (i.e. increase carrier concentration)?

Assume photogeneration of 10^{16} cm^{-3}

$$\rho = \frac{1}{q\mu_n n_o + q\mu_p p_o} = \frac{1}{qn_o(\mu_n + \mu_p)} =$$
$$= \frac{1}{1.6 \times 10^{-19} \times 10^{16} (1350 + 480)} = 0.34 \Omega \cdot \text{cm}$$

$$R = \rho \frac{L}{A} = 0.34 \frac{1.0}{10^{-2}} = 34 \Omega$$

$$I = \frac{V}{R} = \frac{10}{34} = 294 \text{ mA}$$




Current has increased ~ 600,000 times. What uses could have this device?

To explore more the EM spectrum, download this desktop Java App

Electromagnetic Waves **Wavelength Calculator** Select:

$\lambda = 749.481144 \times 10^{-9} \text{ [m]}$

Phase velocity $v_p = 2.99792458 \times 10^8 \text{ m/s}$
Wave Period $T_p = 2.5 \times 10^{-15} \text{ s}$
Photon Energy $E_{ph} = 1.65426708 \text{ [eV]}$



400 THz 450 THz 500 THz 550 THz 600 THz 650 THz 700 THz 750 THz

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Frequency $f = 400.0 \times 10^{12} \text{ [Hz]}$
 $= 400.0 \text{ [THz]}$

VISIBLE SPECTRUM
400 THz - 789 THz

Red Band: 400 THz - 484 THz (750 nm - 620 nm)
AlGaAs - AlGaInP Lasers (~ 630 to 900 nm)

Relative Dielectric Constant $\epsilon_r =$ Conductivity $\sigma =$ S/m

Steady State Carrier Generation

- **After analyzing the transient decay of an excess electron-hole pair (EHP) population, we now look at the steady-state regime.**

Again, we give another look at thermal equilibrium.

At any temperature T there is a thermal generation rate

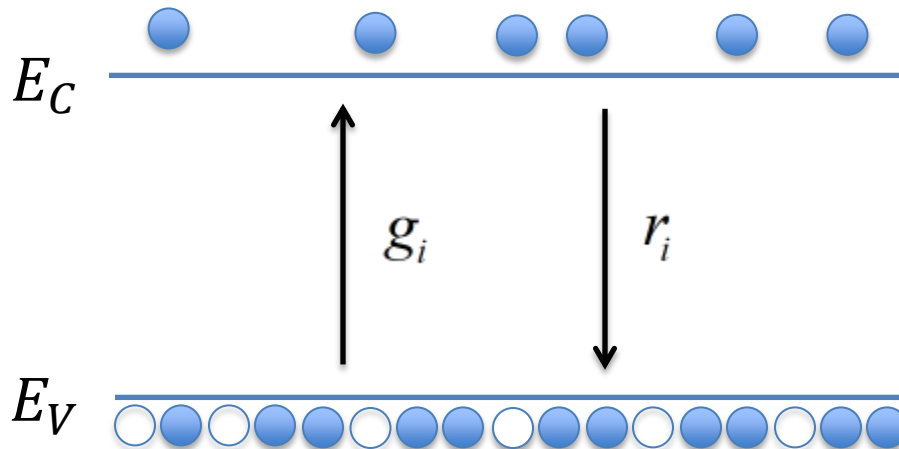
$$g(T) = g_i$$

Steady-state thermal equilibrium

Thermal recombination rate = thermal generation rate

$$r_i = \alpha_r n_o p_o = \alpha_r n_i^2 = g_i$$

with α_r a proportionality constant.



Steady-state generation of excess EHP

Total generation rate

$$\underbrace{g(T)}_{\text{thermal generation}} + \underbrace{g_{op}}_{\text{optical generation}} = \alpha_r \underbrace{n_o}_{\text{thermal equilibrium}} + \underbrace{\delta n}_{\text{excess generation}} \left(\underbrace{p_o}_{\text{thermal equilibrium}} + \underbrace{\delta p}_{\text{excess generation}} \right)$$

Steady state (and no trapping)

$$\longrightarrow \delta n = \delta p$$

Low-level excitation

$$\cancel{g(T)} + g_{op} = \cancel{\alpha_r n_o p_o} + \alpha_r [(n_o + p_o)\delta n + \underbrace{\delta n^2}_{\text{neglect}}]$$

$$g_{op} = \alpha_r (n_o + p_o) \delta n = \frac{\delta n}{\tau_n}$$

$$\tau_n = \tau_p = \frac{1}{\alpha_r (n_o + p_o)}$$

Steady-state generation of excess EHP

$$g_{op} = \alpha_r (n_o + p_o) \delta n = \frac{\delta n}{\tau_n}$$

Steady-state excess
carrier concentration

$$\delta n = \delta p = g_{op} \tau_n$$

If $\tau_n \neq \tau_p$ (e.g., recombination via traps)

$$\delta n = g_{op} \tau_n$$

$$\delta p = g_{op} \tau_p$$

Photoconductive Devices

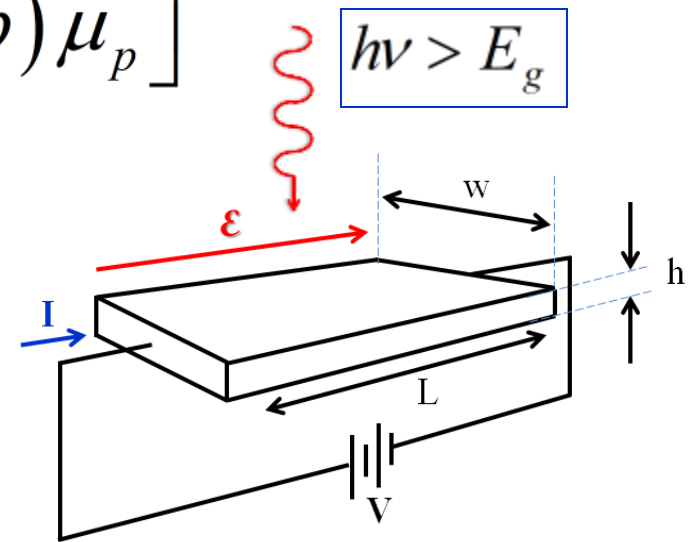
- Conductivity before illumination

$$\sigma = \sigma_n + \sigma_p = q(n\mu_n + p\mu_p)$$

- After illumination, change in conductivity

$$\sigma + \Delta\sigma = q \left[(n + \delta n)\mu_n + (p + \delta p)\mu_p \right]$$

$$\Delta\sigma = q \left[\delta n\mu_n + \delta p\mu_p \right]$$



Photoconductive Devices

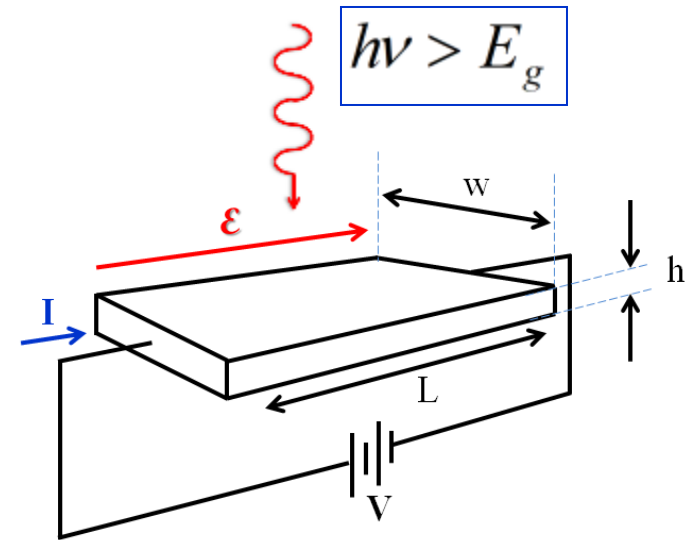
$$\Delta\sigma = q \left[\delta n \mu_n + \delta p \mu_p \right]$$

$$\delta n = g_{op} \tau_n$$

$$\delta p = g_{op} \tau_p$$

$$\Delta\sigma = q g_{op} (\tau_n \mu_n + \tau_p \mu_p)$$

- For high sensitivity
 - High mobility
 - Long recombination times



Some Photoconductive Materials

		E_g (eV)	μ_n (cm ² /V-s)	μ_p (cm ² /V-s)	m_n^*/m_o (m_l, m_t)	m_p^*/m_o (m_{lh}, m_{hh})	a (Å)	ϵ_r	Density (g/cm ³)	Melting point (°C)	
IR	Si	(i/D)	1.11	1350	480	0.98, 0.19	0.16, 0.49	5.43	11.8	2.33	1415
	Ge	(i/D)	0.67	3900	1900	1.64, 0.082	0.04, 0.28	5.65	16	5.32	936
	SiC (α)	(i/W)	2.86	500	—	0.6	1.0	3.08	10.2	3.21	2830
	AlP	(i/Z)	2.45	80	—	—	0.2, 0.63	5.46	9.8	2.40	2000
	AlAs	(i/Z)	2.16	1200	420	2.0	0.15, 0.76	5.66	10.9	3.60	1740
	AlSb	(i/Z)	1.6	200	300	0.12	0.98	6.14	11	4.26	1080
	GaP	(i/Z)	2.26	300	150	1.12, 0.22	0.14, 0.79	5.45	11.1	4.13	1467
	GaAs	(d/Z)	1.43	8500	400	0.067	0.074, 0.50	5.65	13.2	5.31	1238
	GaN	(d/Z, W)	3.4	380	—	0.19	0.60	4.5	12.2	6.1	2530
	GaSb	(d/Z)	0.7	5000	1000	0.042	0.06, 0.23	6.09	15.7	5.61	712
IR	InP	(d/Z)	1.35	4000	100	0.077	0.089, 0.85	5.87	12.4	4.79	1070
	InAs	(d/Z)	0.36	22600	200	0.023	0.025, 0.41	6.06	14.6	5.67	943
	InSb	(d/Z)	0.18	10 ⁵	1700	0.014	0.015, 0.40	6.48	17.7	5.78	525
	ZnS	(d/Z, W)	3.6	180	10	0.28	—	5.409	8.9	4.09	1650*
	ZnSe	(d/Z)	2.7	600	28	0.14	0.60	5.671	9.2	5.65	1100*
VIS	ZnTe	(d/Z)	2.25	530	100	0.18	0.65	6.101	10.4	5.51	1238*
	CdS	(d/W, Z)	2.42	250	15	0.21	0.80	4.137	8.9	4.82	1475
	CdSe	(d/W)	1.73	800	—	0.13	0.45	4.30	10.2	5.81	1258
	CdTe	(d/Z)	1.58	1050	100	0.10	0.37	6.482	10.2	6.20	1098
	PbS	(i/H)	0.37	575	200	0.22	0.29	5.936	17.0	7.6	1119
	PbSe	(i/H)	0.27	1500	1500	—	—	6.147	23.6	8.73	1081
PbTe	(i/H)	0.29	6000	4000	0.17	0.20	6.452	30	8.16	925	

All values at 300 K.

*Vaporizes

Example

- Consider Si at $T=300\text{K}$ and $n_o = 10^{14}\text{cm}^{-3}$
- Optical generation $10^{19}\text{EHP cm}^{-3}/\text{s}$
- Recombination lifetimes

$$\tau_n = \tau_p = 2 \times 10^{-6}\text{s}$$

- **Steady-state concentration**

$$\begin{aligned}\delta n = \delta p &= g_{op}\tau_n = \\ &= 10^{19} \times 2 \times 10^{-6} = 2 \times 10^{13}\text{cm}^{-3}\end{aligned}$$

Example

- Holes equilibrium concentration

$$p_o = \frac{n_i^2}{n_o} = \frac{2.25 \times 10^{20}}{10^{14}} = 2.25 \times 10^6 \text{ cm}^{-3}$$

- Holes total concentration

$$p_o + \delta p = 2.25 \times 10^6 + 2 \times 10^{13} \approx 2 \times 10^{13} \text{ cm}^{-3}$$

- Electrons total concentration

$$n_o + \delta n = 10^{14} + 2 \times 10^{13} = 1.2 \times 10^{14} \text{ cm}^{-3}$$

$$\begin{array}{l} n_o p_o = n_i^2 \\ \longrightarrow np \neq n_i^2 \end{array}$$

Example

- Quasi-Fermi level for electrons

$$n_o + \delta n = n = 1.2 \times 10^{14} \text{cm}^{-3}$$

$$n = n_i \exp \left[\frac{F_n - E_i}{k_B T} \right]$$

$$0.0259 \times \ln \frac{1.2 \times 10^{14}}{1.5 \times 10^{10}} = F_n - E_i$$

$$F_n - E_i = 0.0259 \times \ln(8 \times 10^3) = 0.233 \text{eV}$$

Example

- Quasi-Fermi level for holes

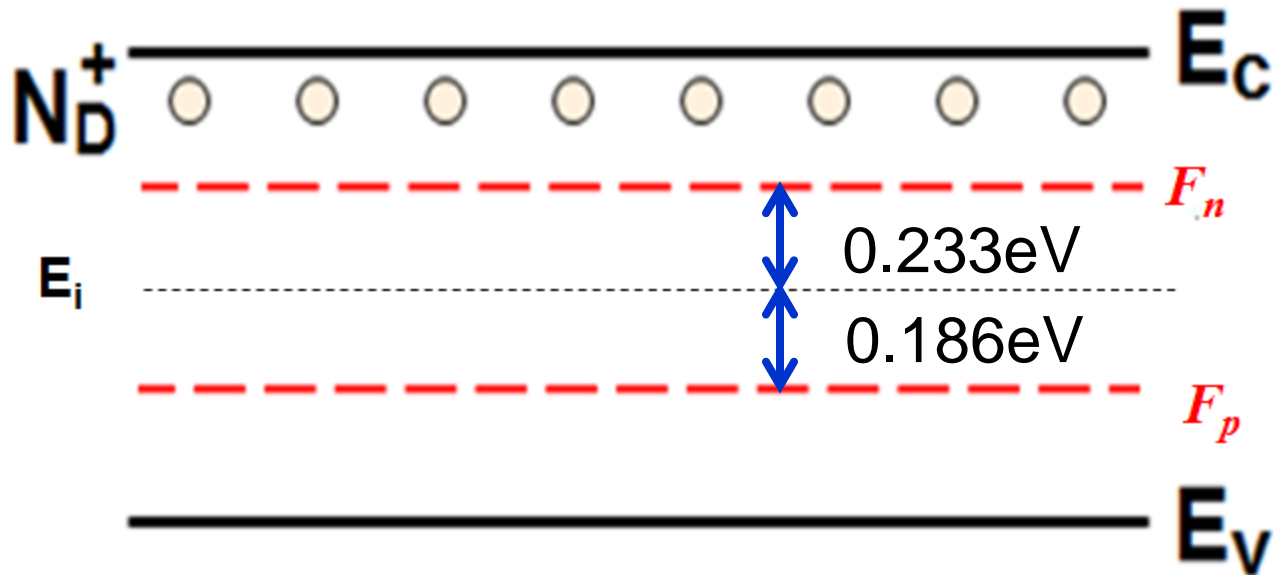
$$p_o + \delta p = p = 2 \times 10^{13} \text{ cm}^{-3}$$

$$p = n_i \exp \left[\frac{E_i - F_p}{k_B T} \right]$$

$$0.0259 \times \ln \frac{2 \times 10^{13}}{1.5 \times 10^{10}} = F_p - E_i$$

$$E_i - F_p = 0.0259 \times \ln(1.3 \times 10^3) = 0.1864 \text{ eV}$$

Example



$$n = n_i e^{(F_n - E_i)/kT}$$

$$p = n_i e^{(E_i - F_p)/kT}$$